



EXPEDITED PROCEDURE - EXAMINING GROUP 2815

S/N 09/826,661

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Yong-Jun Hu Examiner: Joseph Nguyen
Serial No.: 09/826,661 Group Art Unit: 2815
Filed: April 5, 2001 Docket: 303.098US4
Title: LOW ANGLE, LOW ENERGY PHYSICAL VAPOR DEPOSITION OF
ALLOYS

File: 444880.WPD

AMENDMENT & RESPONSE UNDER 37 C.F.R. § 1.116

Box AF
Commissioner for Patents
Washington, D.C. 20231

RECEIVED
AUG 29 2002
TECHNOLOGY CENTER 2800

In response to the final Office Action mailed April 24, 2002, please amend the application as follows.

In the Claims

Please substitute the claim set in the appendix entitled Clean Version of Pending Claims for the previously pending claim set. The substitute claim set is intended to reflect cancellation of claims 31-37, 39-47, and 55-70, and addition of new claims 71-107. Specific amendments to individual claims are detailed in the following marked-up set of claims.

Please add the following new claims:

Sub 71. In a semiconductor device having a substrate, a contact hole in a layer of insulator material directly overlying the substrate, the hole comprising:

a bottom surface having at least one generally planar layer of conductive material including at least two different constituent elements; and

a vertical sidewall consisting substantially entirely of the aforementioned layer of insulator material.

72. The device of claim 71 where the planar layer contacts the lower end of the sidewall.

08/27/2002 AWONDAF1 00000021 09826661

01 FC:102
02 FC:103

84.00 OP
72.00 OP